

Form PTO-1449  <b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b> (Use several sheets if necessary)	ATTY. DOCKET NO. 0171-1098PUS1	APPLICATION NO. NEW
	APPLICANT Takeru WATANABE, et al.	
	FILING DATE May 20, 2004	GROUP

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JSS	US 5,691,100	A	1997-11-25	Kudo, et al.			
	US 5,525,453	A	1996-06-11	Przybilla, et al.			
	US 5,843,319	A	1998-12-01	Przybilla, et al.			
	US 5,612,169	A	1997-03-18	Eichhorn, et al.			
	US 5,529,886	A	1996-06-25	Eichhorn, et al.			
	US 5,442,087	A	1995-08-15	Eichhorn, et al.			
	US 6,703,181	B1	2004-03-09	Hayashi, et al.			
	US 5,658,706	A	1997-08-19	Niki, et al.			
	US 5,744,281	A	1998-04-28	Niki, et al.			
	US 6,004,724	A	1999-12-21	Yamato, et al.			

## FOREIGN PATENT DOCUMENTS

	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
JSS	JP	2-27660	B2	1990-06-19	JAPAN			ABS	
	JP	63-27829	A	1988-02-05	JAPAN			ABS	
	JP	5-232706	A	1993-09-10	JAPAN			ABS	
	JP	5-249683	A	1993-09-28	JAPAN			ABS	
	JP	5-158239	A	1993-06-25	JAPAN			ABS	
	JP	5-249662	A	1993-09-28	JAPAN			ABS	
	JP	5-257282	A	1993-10-08	JAPAN			ABS	
	JP	5-289322	A	1993-11-05	JAPAN			ABS	
	JP	5-289340	A	1993-11-05	JAPAN			ABS	

## OTHER DOCUMENTS (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)

JSS	HINSBERG et al., "Fundamental studies of airborne chemical contamination of chemically amplified resists", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 535-546.
I	KUMADA et al., "Study on over-top coating of positive chemical amplification resists for KrF excimer laser lithography", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 571-574.
I	HATAKEYAMA et al., "Investigation of discrimination enhancement with new modeling for poly-hydroxystyrene positive resists", Journal of Photopolymer Science and Technology, Vol. 13, No. 4, 2000, 519-524.

EXAMINER JCH	DATE CONSIDERED 9/2005
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

GMM

GMM/SM

Form PTO-1449				ATTY. DOCKET NO. 0171-1098PUS1		APPLICATION NO. NEW	
<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>				APPLICANT Takeru WATANABE, et al.			
(Use several sheets if necessary)				FILING DATE May 20, 2004		GROUP	

  

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
J	US 6,261,738	B1	2001-07-17	Asakura, et al.			
	US						
	US						

  

FOREIGN PATENT DOCUMENTS									
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
J	JP	6-194834	A	1994-07-15	JAPAN			ABS	
	JP	6-242605	A	1994-09-02	JAPAN			ABS	
	JP	6-242606	A	1994-09-02	JAPAN			ABS	
	JP	6-263716	A	1994-09-20	JAPAN			ABS	
	JP	6-263717	A	1994-09-20	JAPAN			ABS	
	JP	6-266100	A	1994-09-22	JAPAN			ABS	
	JP	6-266111	A	1994-09-22	JAPAN			ABS	
	JP	7-128859	A	1995-05-19	JAPAN			ABS	
	JP	7-92678	A	1995-04-07	JAPAN			ABS	
	JP	7-92680	A	1995-04-07	JAPAN			ABS	
	JP	7-92681	A	1995-04-07	JAPAN			ABS	
	JP	7-120929	A	1995-05-12	JAPAN			ABS	
	JP	7-134419	A	1995-05-23	JAPAN			ABS	
	JP	2000-314956	A	2000-11-14	JAPAN			ABS	
	JP	9-95479	A	1997-04-08	JAPAN			ABS	
	JP	9-230588	A	1997-09-05	JAPAN			ABS	
	JP	9-208554	A	1997-08-12	JAPAN			ABS	

  

<b>OTHER DOCUMENTS</b> (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)	
JCL	
EXAMINER	DATE CONSIDERED 9/20/05
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

GMM

GMM/sm